

**PHOTORESIST COMPOSITION**

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**Abstract of JP9054432**

**PROBLEM TO BE SOLVED:** To improve the coating performance, soln. stability, etc., of a photoresist compsn.

**SOLUTION:** This compsn. contains a copolymer of a (meth)acrylate monomer having a fluoroalkyl group with an ethylenically unsatd. monomer having a silicone chain and a (meth)acrylate monomer having a polyoxyalkylene group. This compsn. does not cause unevenness in the thickness of a coating film or striation at the time of spin coating and enables uniform coating.

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